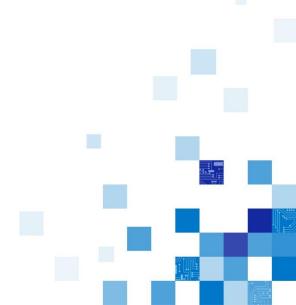


LLC DRAM Updates

Mar. 2022 | DRAM Product Planning Team, Memory Division



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Updates on Footprint

1. Die size: 10 x 5 mm

2. Footprint study of LLC DRAM includes

1) The same OD-ECC scheme as HBM3

□ OD-ECC: 256b (data) + 16b (meta data for system) + 32b (ECC check bits)

2) The repair and check scheme: PPR, Line Repair and Boundary Scan

3. Footprint study of LLC DRAM does not include

1) DFT scheme, e.g. DA or MBIST: Die size increases if DFT scheme is implemented

Channel

| Cell | Cell | Cell | Cell |
|-----------|-----------|-----------|-----------|
| Pad(Peri) | Pad(Peri) | Pad(Peri) | Pad(Peri) |
| Pad(Peri) | Pad(Peri) | Pad(Peri) | Pad(Peri) |
| Cell | Cell | Cell | Cell |
| Cell | Cell | Cell | Cell |
| Pad(Peri) | Pad(Peri) | Pad(Peri) | Pad(Peri) |
| Pad(Peri) | Pad(Peri) | Pad(Peri) | Pad(Peri) |
| Cell | Cell | Cell | Cell |

| Key Features | Value |
|--------------|-------------|
| Cache line | 64B |
| Organization | x1024 |
| Density | 8Gb |
| Ch. | 16 |
| Bank/Ch. | 4 (2 BGs, |
| Dalik/Cii. | 2 Banks/BG) |
| BL | 8 |
| Bandwidth | 0.8~1TB/s |
| Pin speed | 6.4~8Gbps |
| tRC | 40ns |
| RL (tRCD+RL) | 32ns Con |

Further Study Results

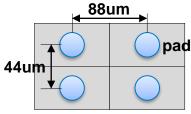
1. Power Rail

- 1) If Intel shares power measurement conditions, Samsung team can estimate the power of LLC DRAM
 - □ For example, 3 channels are operated and the remaining channels are in precharge standby (IDD2N)

| Power Supply | Typical |
|--------------|---------|
| VDDP | 1.8V |
| VDDC / VDDQ | 1.1V |
| VDDQL | 0.4V |

2. Pad pitch: 88 x 44 um

1) Does Intel consider HCB (hybrid copper bonding)?



3. Operating temperature: 105C (t_i) w/ 4x refresh rate

Product and Stacking Type

1. Product type: Wafer or Die w/ ubump



2. Stacking type: 2.5D and/or 3D

1) For 3D stacking, we need to discuss about how to build DA path (for the purpose of test and/or failure analysis)

| 2 ED Stocking | 3D Stacking | | |
|--|-----------------------|--|--|
| 2.5D Stacking | DA path as TSV in CPU | DA path as additional connection | |
| (Logic) Interposer CPU LLC PCB DA pin | CPU TSV in CPU | CPU TBD Wire bonding? - Additional Interposer? - etc | |

Discussion about DFT

1. Need to discuss about DFT scheme for HF (high frequency)

- 1) LF test is done at wafer level
 - ☐ HF test at wafer level needs further study about feasibility (currently at conceptual stage)
- 2) Die overhead of DFT for HF depends on test coverage (function)

| | Option 1 – Design guarantee | Option 2 – DA | Option 3 – MBIST (+ DA) |
|--------------|---|-----------------------------------|--|
| How to test | HF yield is measured as SiP or proxy PKG (Yield level needs to be agreed) | Test patterns are injected via DA | Test is initiated by simple command via DA |
| Die overhead | None | Mid | High |

Requests for Intel

1. Proposal on separate meeting for standardization milestone

1) To align Standardization schedule btw Intel & Samsung

2. Requirements for DFT coverage

- 1) Test coverage (functions)
 - ☐ For example, the same level as HBM
 - □ # of DA pads

3. Quick question for Intel Market rough estimate

- 1) 02/22 "For a iGFX attach to client PCs" → Market for iGPU frame buffer memory?
- 2) 03/17 − "Graphics Volume 10-20Mu" → Market for dGPU memory + Accelerator (next PVC) memory?

END

Comparison between LLC and HBM3

| | Item | HBM3 | LLC DRAM |
|------------------------|-----------------|--|-----------------------------------|
| Architecture | Die composition | Stack, 8H | Mono |
| | Cache line | 32B | 64B |
| | Footprint | 115.56mm² 10.75(X) * 10.75(Y) | 50mm ² 10(X) * 5(Y) |
| | Density | 16Gb | 8Gb |
| | Organization | x1024 | x1024 |
| | CH per die | 4 | 16 |
| | PCH per die | 2 | 1 |
| | Bank per die | 128 | 64 (32BG, 2Banks/BG) |
| | BL | 8 | 8 |
| | Interface | DRAM type | ← |
| | PHY pitch | 110um x 48um | 88um x 44um |
| | Bandwidth | 0.8TB/s | 0.8~1TB/s |
| | Power/bit | 4pj/bit | 0.8pJ/bit |
| _ | Pin speed | 6.4Gbps | 6.4~8Gbps |
| Features | tRC | 52ns | 40ns |
| | RL (tRCD+RL) | 35ns | 30ns |
| | WL (tRCD+WL) | 20ns | 16ns |
| Operating Condition | VDD1 / VDD2 | 1.8V / 1.1V | ← |
| | VDDQ | 0.4V | ← |
| | Operating Temp | 0~95°C | -25~105°C |
| | RAS | OD-ECC | ← |
| Special Feature | TEST | Boundary Scan, Lane Repair, PPR, Direct Access, BIST, IEEE 1500 | Boundary Scan, Lane Repair, PPR |

ARs continued

AR: Intel to provide update on Size and Timing of Market to help Samsung with Motivation for TCM.

- Rough Estimate
 - For 50mm2 die with 2026/27 Server intercept. Multiple GB per socket
 - Low market penetration. 6M unit, High Market Penetration. 60M unit
 - For a iGFx attach to client PCs. ~5M unit

 Any deeper discussion would be with Business Teams (Raja K) as Intel team on call is engineering team

Graphics feedback

- Capacity
 - varies across product lines from 2GB to 32GB
- BW/capacity ratio
 - Ideal BW/capacity ratio varies across product lines from .5 to 1 to 2 TB/s/GB
 1 TB/s/GB is good except for high end

 - 2 TB/s/GB for high end OAM form factor with limited footprint for memory
- Aspect ratio
 - For 50mm2 aspect ratio of 10x5mm is good. 10x10mm is too large
- Volume
 - 10-20Mu
- Timeline
 - 2026

LLC DRAM Feature Alignment

1. Need to confirm the LLC DRAM key requirement

- 1) To fix the starting point for the design optimization
 - □ For server/client CPU, 1GB, 0.8TB/s and 50mm2, is agreed as starting point for further discussion. And How about AI/ML Accelerator?

2. Next step: To investigate the detailed architecture

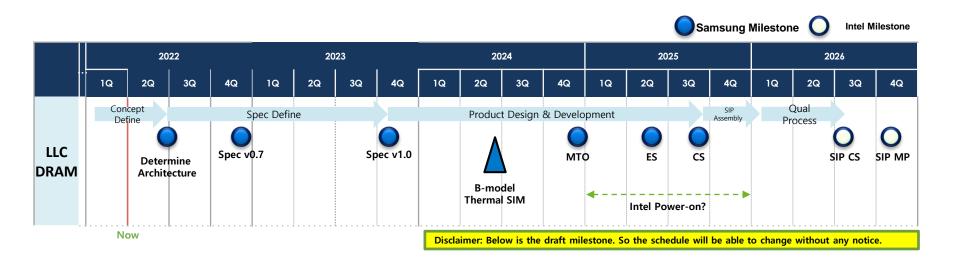
1) Power rail, on top of concrete high-level DRAM architecture

| | Server / Client CPU | AI/ML Accelerator | Remarks | |
|----------------------------|---------------------------------------|--------------------------|---|--|
| Die composition | Mono-die | Mono-die | - | |
| Cache line | | 64B | Need to discuss about Cache line of Accelerator | |
| Footprint | 50mm² | | Need to discuss about Range | |
| Density | 1GB | | Under 1GB is OK? | |
| Latency | tRC: 40-45ns / tRCD: 17ns / tAA: 15ns | | Need to update AI/ML Accelerator requirement | |
| Bandwidth (6.4Gbps/pin) | 1TB/s | | | |
| Ю | Distributed, 1K | Distributed, 4K | | |
| Channel | TBD | TBD | | |
| Bank | based on Cache line size | based on Cache line size | TBU after Key Architecture fixed | |
| BL | Any preference? BL8 vs BL16 | Any preference? | The after key Architecture fixed | |
| Address | TBD | TBD | | |
| Power rail/Pin map | TBD | TBD | | |

LLC DRAM Milestone Update

1. Spec v0.7 & MTO draft milestone are updated → Need to align with Intel

1) Power-on : 2025 → Any quarter based schedule?



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